

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|---|---|------------------|
| 1 | 2090 | oxide same surface near3 charge | USPAT; US-PGPUB | 2003/12/11 15:29 |
| 9 | 0 | UV same charge same (DC and RF) same (electron adj beam) | USPAT; US-PGPUB | 2003/12/11 15:29 |
| 2 | 66 | (oxide same surface near3 charge) and hydrofluoric and silicon and dioxide | USPAT; US-PGPUB | 2003/12/11 15:29 |
| 3 | 105 | vapor and hydrofluoric and ((silicon adj dioxide) or "SiO.sub.2") and (UV adj radiation) and etch\$3 | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 4 | 31 | (vapor near2 (hydrofluoric or HF)) and ((silicon adj dioxide) or "SiO.sub.2") and (UV adj radiation) and etch\$3 | USPAT; US-PGPUB | 2003/12/11 15:36 |
| 5 | 90 | (wafer and cleaning and HF and water and vapor) and (uv adj radiation) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 6 | 32 | (oxide same surface near3 charge) same (electron adj beam) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 7 | 35 | (oxide same surface same charge same positive) same (electron adj beam) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 8 | 8 | (dioxide same surface same charge same positive) same (electron adj beam) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 10 | 25 | charge same (DC and RF) same (electron adj beam) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 11 | 262 | (positive adj charge) same (electron adj beam) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 12 | 961 | (oxide same surface near3 charge) and (H2O or "H.sub.2O" or water) | USPAT; US-PGPUB | 2003/12/11 15:30 |
| 13 | 173 | (oxide same surface near3 charge) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric) | USPAT; US-PGPUB | 2003/12/11 15:31 |
| 14 | 107 | ((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)).ab. | USPAT; US-PGPUB | 2003/12/11 15:35 |
| 15 | 1249 | ((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)).clm. | USPAT; US-PGPUB | 2003/12/11 15:34 |
| 17 | 5 | ((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric) and monolayer).clm. | USPAT; US-PGPUB | 2003/12/11 15:35 |
| 18 | 5 | ((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric) and monolayer).clm. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:35 |
| 19 | 1548 | ((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)).ab. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/11 15:36 |
| 20 | 172 | (vapor near2 (hydrofluoric or HF)) and ((silicon adj dioxide) or "SiO.sub.2") and charge | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:37 |
| 21 | 46 | (vapor near2 (hydrofluoric or HF)) and ((silicon adj dioxide) or "SiO.sub.2") and monolayer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:37 |
| 22 | 46 | (216/73).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:38 |
| 23 | 1069 | (216/79).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:39 |

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| 24 | 205 | (216/80).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:39 |
| 25 | 1304 | (438/706).CCLS. | USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:40 |
| 26 | 323 | (438/743).CCLS. | USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:40 |
| 27 | 2135 | (134/2).CCLS. | USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:45 |
| 28 | 612 | (134/31).CCLS. | USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/12/11 15:46 |